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The following is a complete listing of all claims in the application, with an indication of the status of each:

Listing of claims:

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1. (currently amended) A magnetoresisfive effect sensor using a shieldedtype magnetoresistive effect element comprising:

a magnetoresistive effect film above a lower shield layer, said film comprising a basic configuration that is a combination of a free layer, a barrier layer, and a fixed layer, wherein either a combination of a free layer, a said barrier layer is formed on said free layer, and a said fixed layer is formed on said barrier layer, or a combination of a fixed layer, a said barrier layer is formed on said fixed layer, and a said free layer is formed on said barrier layer, said barrier layer inheriting a roughness of said lower shield layer, wherein a sensing current flows substantially perpendicularly with respect to said magnetoresistive effect film, and wherein either an amorphous material or a microcrystalline material is used in a said lower shield layer so as to smooth said lower shield layer, thereby increasing the smoothness of said barrier layer.

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- 2. (original) A magnetor sistive effect sensor according to claim 1, wherein said lower shield comprises a crystal grain diameter of 6.2 nm or smaller.
- 3. (currently amended) A magnetoresistive effect sensor according to claim 1 or claim 2, wherein said lower shield is made of a material of CoZrTa, with a and CoZrTaCr alloy, serving as a base layer for said free layer.
- 4. (withdrawn) A magnetoresistive effect sensor according to claim 1, wherein said lower shield is formed by means of sputtering.

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5. (withdrawn) A magnetoresistive effect sensor according to claim 1, wherein a magnetoresistive effect film having a basic configuration that is either a combination of a free layer, a barrier layer formed on said free layer, and a fixed layer formed on said barrier layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer is formed on said lower shield directly or formed thereon via an intervening base layer.

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6. (withdrawn) A magnetoresistive effect sensor according to claim 1, wherein a lower conductor layer is disposed at a bottom part of a magnetoresistive effect film having a basic configuration that is either a combination of a free layer, a barrier layer formed on said free layer, and a fixed layer formed on said barrier layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer, a bottom part of said lower conductor layer being in contact with a

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8 lower shield.

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7. (withdrawn) A magnetoresistive effect sensor wherein in a magnetoresistive effect element in which a conductor layer is disposed at a bottom part of a magnetoresistive effect film having a basic configuration that is either a combination of a free layer, a barrier layer formed on said free layer, and a fixed layer formed on said barrier layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer, in contact either with an intervening base layer or directly therewith, wherein said lower conductor layer functions as a lower electrode to cause a sensing current to flow in said magnetoresistive effect film, and

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further wherein a lower conductor is made of a material selecting from a group consisting of an amorphous material and a microcrystal.

- 8. (withdrawn) A magnetoresistive effect sensor according to claim 7, wherein said microcrystal forming said lower conductor layer comprises a crystal grain diameter of 5.4 nm or smaller.
- 9. (withdrawn) A magnetoresistive effect sensor according to claim 7, wherein said lower conductor layer is formed by sputtering.
 - 10. (withdrawn) A magnetoresistive effect sensor according to claim 1, further comprising a layer which fixes a magnetization of a fixed layer, provided so as to be in contact with said fixed layer.

11. (withdrawn) A method for manufacturing a magnetoresistive effect sensor whereby a shielded-type magnetoresistive effect element in which a sensing current flows substantially perpendicular to a magnetoresistive effect film, using a magnetoresistive effect film having a basic configuration that is either a combination of a free layer, a barrier layer formed on said free layer, and a fixed layer formed on said barrier layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer, wherein a material selected from a group consisting of an amorphous material and a microcrystalline material is used in a lower shield.

12. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 11, wherein said microcrystal used in said lower shield comprises a crystal grain diameter of 6.2 nm or smaller.

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13. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 11, wherein said lower shield is formed using sputtering.

14. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 11, wherein a magnetoresistive effect film having a basic configuration that is either a dombination of a free layer, a barrier layer formed on said free layer, and a fixed layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer is formed on said

lower shield directly or formed thereon via an intervening base layer.

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15. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 11, whereby a lower shield layer is formed and a lower conductor layer is formed on said lower shield layer, and further whereby a magnetoresistive effect film having a basic configuration that is either a combination of affree layer, a barrier layer formed on said free layer, and a fixed layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer is formed on said lower conductor layer, either directly or via an intervening base layer.

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16. (withdrawn) A method for manufacturing a magnetoresistive effect sensor whereby a magnetoresistive effect film having a basic configuration that is either a combination of a free layer, a barrier layer formed on said free layer, and a fixed layer, or a combination of a fixed layer, a barrier layer formed on said fixed layer, and a free layer formed on said barrier layer is formed either/directly on a lower conductor layer or thereonto with an intervening base layer, and further wherein, said lower conductor layer being

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made of a material selected from a group consisting of an amorphous material and a microcrystalline material.

17. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 16, whereby said lower conductor layer is formed by a microcrystal comprising a crystal grain diameter of 5.4 nm or smaller.

18. (withdrawn) A method for manufacturing a magnetoresistive effect sensor according to claim 16, whereby said lower conductor layer is formed by sputtering.

19. (withdrawn) A method for manufacturing a magnetoresistive effect film according to claim 11, whereby a layer fixing a magnetization of a fixed layer is further formed, so as to be in contact with said fixed layer.

20. (withdrawn) A magnetoresistance detection system comprising a magnetoresistive effect sensor according to claim 1, a means for generating a current passing through a magnetoresistive effect sensor, and means for detecting a change in magnetoresistance of said magnetoresistive effect sensor as a function of a detected magnetic field.

21. (withdrawn) A magnetic recording system comprising a magnetic storage medium comprising a plurality of tracks for data recording, a magnetic recording system for storing data on said magnetic storage medium, a magnetoresistance detection system according to claim 20, and an actuating means lined to said magnetic recording system and a magnetoresistance conversion system for the purpose of causing said magnetic recording system

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and said magnetoresistance detection system to move to a selected track of said magnetic storage medium.